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(54) Title: LIQUID CRYSTAL POLYMERS FOR FLEXIBLE CIRCUITS

(57) Abstract: A process for providing a metal-seeded liquid crystal polymer comprises the steps of providing a liquid crystal polymer substrate, applying an aqueous solution comprising an alkali metal hydroxide and a solubilizer, to etch the liquid crystal polymer substrate, and depositing an adherent metal layer on the etched liquid crystal polymer substrate using electroless metal plating or vacuum deposition of metal. When using electroless metal plating, a tin(II) solution applied to the liquid crystal polymer substrate, followed by application of a palladium(II) solution, provides a metal-seeded liquid crystal polymer. An aqueous solution, comprising from 35wt.% to 55wt.% of an alkali metal salt, and from 10wt.% to 35wt.% of a solubilizer, provides an etchant for the liquid crystal polymer at temperatures from 50°C to 120°C. A flexible circuit comprising a liquid crystal polymer film having through-holes and related shaped voids may be formed using the etchant compositions previously described.

LIQUID CRYSTAL POLYMERS FOR FLEXIBLE CIRCUITS

Field of the Invention

The invention relates to low dielectric constant films suitable for use in flexible
5 circuit applications and more particularly to chemical etching of flexible films and
composites that include liquid crystal polymers (LCP).

Background to the Invention

10 An etched copper or printed polymer thick film circuit pattern over a polymer film
base may be referred to as a flexible circuit or flexible printed wiring. As the name
suggests, flexible circuitry can move, bend and twist without damaging the conductors to
permit conformity to different shapes and unique package sizes. Originally designed to
replace bulky wiring harnesses, flexible circuitry is often the only solution for the
15 miniaturization and movement needed for current, cutting-edge electronic assemblies.
Thin, lightweight and ideal for complicated devices, flexible circuit design solutions range
from single-sided conductive paths to complex, multilayer three-dimensional packages.

Commonly used dielectric film base materials for flexible electronic packaging
include polyimide, polyester terephthalate, random-fiber aramid and polyvinyl chloride.
20 Changes in electronic device design create the need for new materials with properties
surpassing the electrical performance and processing capabilities of the substrates listed
previously. For example, a lower dielectric constant allows faster electrical signal transfer,
good thermal performance facilitates cooling for a package, a higher glass transition or
melting temperature improves package performance at higher temperature, and lower
25 moisture absorption leads to signal and data processing at higher and higher frequencies.

Polyimide film is a commonly used substrate for flexible circuits that fulfil the
requirements of complex, cutting-edge electronic assemblies. The film has excellent
properties such as thermal stability and low dielectric constant, but represents a limiting
factor to additional gain in the speed or frequency at which electronic components may
30 operate. A major drawback to further progress using polyimide film relates to the way in
which polyimide absorbs moisture to levels that interfere with high frequency device

performance. Higher frequency operation will require the identification or development of substrate materials with less susceptibility to moisture absorption.

Liquid crystal polymer (LCP) films represent suitable materials as substrates for flexible circuits having improved high frequency performance. Generally they have lower dielectric loss, and absorb less moisture than polyimide films. These beneficial properties of liquid crystal polymers were known previously but difficulties with processing prevented application of liquid crystal polymers to complex electronic assemblies.

The development of multiaxial, e.g. biaxial, film processing techniques expanded the use of liquid crystal polymer film for flexible circuit applications. United States Patent No. 4,975,312 describes a printed wiring board substrate prepared from a multiaxially oriented thermotropic liquid crystalline polymer film having a tailored coefficient of thermal expansion in the X-Y direction and a thickness of not more than about 100 μ m. Materials of this type offer several potential advantages over polyimide films as flexible circuit substrates. Such potential advantages led to the use of readily available processing techniques for producing single layer or multilayer circuit structures supported by one or more layers of a liquid crystal film substrate. A multilayer flexible circuit is a combination of three or more layers of single or double-sided flexible circuits laminated together and processed with drill and plating to form plated through-holes. This creates conductive paths between the various layers without having to use multiple soldering operations.

Reference to drilling for the formation of through-holes reflects the emphasis on physical methods such as mechanical drilling, punching, laser ablation and plasma drilling for via and related circuit feature formation in liquid crystal polymer films. An alternative to conventional drilling and related techniques for hole formation in flexible circuit substrates was introduced as Y-FLEX™ by Yamaichi Corporation. Information describing Y-FLEX™ presents it as a microvia flexible wiring board using LCP resin insulation material and employing an internal conductive bump layer connection. Interconnection of Y-FLEX™ multilayer circuits occurs by conductive bumps penetrating through insulating LCP layers without the need for through-holes.

Although the several physical methods outlined above produce holes and related shaped voids in LCP, there are no reports of chemical methods for producing flexible circuits using liquid crystalline polymer substrates. Chemical etchant solutions for

polyimide substrates are well known for production of polyimide-based flexible circuits. However, as shown in European Patent Application No. EP 0832918 A1, there is no single etchant composition capable of effecting development of circuit features in all types of polyimide. It appears that selection of etchant solutions depends upon the materials used for preparing a specified polyimide. Also aqueous developable photoresists disintegrate under the vigorous attack of etchant compositions described in the published application (EP 0832918).

Having less solubility than polyimide films, liquid crystal polymer films cannot be processed effectively using in-line chemical systems and known etchant compositions.

There appears to be only limited information referring directly to etchant compositions for liquid crystal polymers. United States Patents U.S. 5,891,795 and U.S. 5,896,899 describe a metallization process making reference to liquid crystal polymers among a number of suitable substrates. The metallization process includes electroless deposition or vacuum deposition of a seed layer to be augmented with additional metal layers using conventional plating techniques. A function of the seed layer is to provide an adhesive link between the plated layers and the substrate. However, there is nothing to demonstrate how well the seed layer adheres to any of the substrates listed by either of the references. Published application WO 99/39021 describes electrolytic plating of elemental palladium either sputtered or ion-plated on the surface of liquid crystal polymers.

United States Patent U.S. 5,443,865 describes a relatively complex process for applying metal seed layers to substrates. Reference to liquid crystal polymers is absent from all but the patent claims. European patent application EP 1069209 describes the plating of plastics using catalytic filler contained within the plastic. Formation of a metal layer on a liquid crystal plastic requires treatment with an alkaline solution to dissolve the plastic followed by treatment with acid to activate the exposed catalyst. The exposed catalyst induces metal deposition from an electroless metal plating bath. There is no suggestion that treatment in alkaline solution affects the adhesion of metal to plastic. Such consideration would not be necessary since the plastic acts as a binder to hold catalytic filler particles.

As well as the need for novel chemical surface treatments of liquid crystal polymers, the need exists to use chemical shaping by e.g. chemical etching to introduce selected features into liquid crystal substrates. There are no reports of chemically etching

liquid crystal polymer films to form features such as through holes. Chemical etching to form through holes in flexible circuit substrates is advantageous because it leads to the formation of unsupported or cantilevered lead structures, which cannot be produced by conventional physical methods.

5 Since some steps of physical drilling and related processes tend to involve expensive equipment, set apart from the main flex circuit production line, there is a need for a more cost effective method for producing flexible circuits using liquid crystal polymer substrates. A further benefit would be the provision of flexible circuits, including unsupported leads.

10

Summary of the Invention

The present invention provides an aqueous-based chemical solution for controllable etching of through-holes and other shaped voids in films comprising liquid crystal polymers (LCP) as flexible circuit substrates. LCP films may be etched at rates
15 exceeding those currently attainable with Kapton polyimide film. This results from adjusting the composition of the chemical etch solution. The new etchant makes possible the alternative use of LCP film to replace polyimide as an etchable substrate for flex circuit manufacture, especially high performance flex circuits. Chemically etched LCP
20 flexible circuits will meet the needs of more sophisticated electronic assemblies, satisfying new opportunities that exist beyond the capabilities of polyimide and LCP film processed using drilling, laser ablation and related conventional physical methods.

The highly alkaline developing solution, referred to herein as an etchant, comprises an alkali metal salt and a solubilizer. A solution of an alkali metal salt alone may be used
25 as an etchant for polyimide but is ineffective for developing LCP in the absence of the solubilizer. Typically the solubilizer is an amine compound preferably an alkanolamine. The efficacy of an amine in an etchant solution according to the present invention depends upon its use with a relatively narrow range of concentrations of alkali metal salts including an alkali metal hydroxide particularly potassium hydroxide. This suggests that there is a
30 dual mechanism at work for developing flex circuits based upon liquid crystal polymers, i.e. the amine acts as a solubilizer for the LCP but preferably within a limited range of concentrations of alkali metal salt in aqueous solution. Discovery of a limited range of

etchant solutions allows the manufacture of flexible printed circuits having finely structured features previously unattainable using current methods, of drilling, punching or laser ablation. The use of aqueous etchant solutions and methods according to the present invention produced flexible circuits including unsupported leads (also known as
5 cantilevered leads) and vias with angled sidewalls which cannot be achieved using the previously mentioned physical methods.

The present invention provides a process that allows selective plating of metal trace patterns on LCP film. Using an additive technique, the process requires initial film surface modification with an etchant composition comprising an alkali metal salt and a
10 solubilizer, as described previously, before the application of material that provides catalytic sites for metal deposition. Formation of catalytic sites may also be referred to as metal seeding. Further processing of a catalyzed liquid crystal polymer surface produces a pattern of circuit traces. Required steps include lamination of a resist over a catalyzed surface and development of a pattern in the resist. The development process exposes
15 catalyzed sites on the liquid crystal polymer. A number of metal deposition steps may then be needed to add metal according to the pattern formed in the resist. Metal deposition may be accomplished using a combination of techniques including electroless plating and electrolytic plating to produce metal traces corresponding to the pattern of the catalyzed sites. The process limits exposure of the substrate to elevated temperature.

20 A process for producing a metal-seeded liquid crystal polymer comprises the steps of, providing a liquid crystal polymer substrate for treatment by applying an aqueous solution comprising an alkali metal hydroxide and a solubilizer to the liquid crystal polymer substrate to provide an etched liquid crystal polymer substrate. Further treatment of the etched liquid crystal polymer substrate involves depositing an adherent metal layer
25 on the etched liquid crystal polymer substrate. An adherent metal layer may be deposited using either electroless metal plating or vacuum deposition of metal such as by sputtering.

When using electroless metal plating, the process for producing a metal-seeded liquid crystal polymer comprises the steps of providing a liquid crystal polymer substrate to which an aqueous solution comprising from 40wt% to 50wt% of potassium hydroxide
30 and from 10wt% to 35wt% of ethanolamine is applied to provide an etched liquid crystal polymer substrate. Applying a tin(II) solution to the etched liquid crystal polymer

substrate followed by a palladium(II) solution provides the metal-seeded liquid crystal polymer.

5 The surface treatment of liquid crystal polymer substrates uses an etchant composition comprising a solution in water of from 35wt.% to 55wt.% of an alkali metal salt, and from 10wt.% to 35wt.% of a solubilizer dissolved in the solution to provide the etchant composition suitable for etching the liquid crystal polymer at a temperature from 50°C to 120°C.

10 Liquid crystal polymers may be etched with etchant compositions according to the present invention to provide a flexible circuit comprising a liquid crystal polymer film having through-holes and related shaped voids formed therein using an etchant composition comprising a solution in water of from 35wt.% to 55wt.% of an alkali metal salt; and from 10wt.% to 35wt.% of a solubilizer dissolved in the solution to provide the etchant composition suitable for etching the liquid crystal polymer at a temperature from 50°C to 120°C.

15 The invention also includes a process for etching a pattern in a liquid crystal polymer. Suitable process steps include, providing a liquid crystal polymer; applying a layer of photoresist to the liquid crystal polymer; exposing the photoresist to a pattern of radiation to crosslink portions of the photoresist exposed to the radiation and using a developer solution to remove unexposed photoresist. This exposes portions of the liquid
20 crystal polymer which may be etched by contact, at a temperature from 50°C to 120°C, with an etchant composition comprising a solution in water of from 35wt.% to 55wt.% of an alkali metal salt; and from 10wt.% to 35wt.% of a solubilizer dissolved in the solution. The etchant composition etches previously unexposed portions of the liquid crystal polymer, either by immersion in the etchant or using spray etching techniques.

25 As used herein all amounts included as percentages refer to weight percent of a designated component.

Detailed Description of the Invention

30 The present invention provides a film substrate for flexible circuits capable of operating at higher frequencies than currently available flex circuit substrates, particularly polyimide films such as KAPTON™ and APICAL™. Attainment of higher frequency

performance, in response to the demand for faster electronic devices, results from the gradual development of methods for processing liquid crystal polymers that were once considered to be relatively intractable. A process development, described in United States Patent 4,975,312, provided multiaxially (e.g. biaxially) oriented thermotropic polymer films of commercially available liquid crystal polymers (LCP) identified by the brand-
5 names VECTRA® (naphthalene based, available from Hoechst Celanese Corp.) and XYDAR® (biphenol based, available from Amoco Performance Products). Multiaxially oriented LCP films of this type represent suitable substrates for flexible printed circuits and circuit interconnects. Characteristics of LCP films include electrical insulation,
10 moisture absorption less than 0.5% at saturation, a coefficient of thermal expansion approaching that of the copper used for plated through holes, and a dielectric constant not to exceed 3.5 over the functional frequency range of 1kHz to 45GHz.

The development of multiaxially oriented LCP films, while providing a film substrate for flexible circuits, was subject to limitations in methods for forming such
15 flexible circuits. An important limitation was the lack of a chemical etch method for use with LCP. Without this technique, complex circuit structures such as unsupported, cantilevered leads or through holes or vias having angled sidewalls cannot be included in a printed circuit design.

Advancements according to the present invention now provide an aqueous-based
20 chemical solution for controllable etching of unsupported leads, through-holes with angled sidewalls, and other shaped voids in films comprising multiaxially oriented, thermotropic, liquid crystal polymers as flexible circuit substrates. After processing by chemical etching, flexible circuits using LCP film substrates possess all of the benefits of similarly processed polyimide films with the additional benefits of higher frequency operation along with, and
25 because of, lower moisture absorption.

Flexible circuit structures according to the present invention result from etching a LCP polymer film during contact of the film with an aqueous alkaline etchant at a temperature of from 50°C (122°F) to 120°C (248°F). The formation of unsupported leads, through holes and other circuit features in the LCP film requires protection of portions of
30 the polymeric film using a mask of a photo-crosslinked negative acting, aqueous processible photoresist. During the etching process the photoresist exhibits substantially no swelling or delamination from the LCP polymer film.

Negative photoresists suitable for use with liquid crystal polymers according to the present invention include negative acting, aqueous developable, photopolymer compositions such as those disclosed in U.S. Pat. Nos. 3,469,982, 3,448,098, 3,867,153, and 3,526,504. Such photoresists include at least a polymer matrix including crosslinkable monomers and a photoinitiator. Polymers typically used in photoresists include copolymers of methyl methacrylate, ethyl acrylate and acrylic acid, copolymers of styrene and maleic anhydride isobutyl ester and the like. Crosslinkable monomers may be multiacrylates such as trimethylol propane triacrylate.

Commercially available aqueous base, e.g. sodium carbonate developable, negative acting photoresists employed according to the present invention include polymethylmethacrylates such as RISTON photoresist materials e.g. RISTON 4720 available from duPont de Nemours and Co. Other useful examples include AP850 available from LeaRonol Inc. and PHOTEC HU350 available from Hitachi Chemical Co. Ltd. Photoresist compositions using the tradename AQUAMER are available from Hercules Inc. There are several series of AQUAMER photoresists including the "SF" and "CF" series with SF120, SF125, and CF2.0 being representative of these materials.

Polyimide films may be etched using solutions of potassium hydroxide alone, as described in mutually owned United States Patent No. 5,227,008. However, liquid crystal polymers are unaffected by potassium hydroxide and require highly alkaline aqueous etchant solutions according to the present invention comprising water soluble salts of alkali metals and ammonia combined with a solubilizer for the LCP film. Suitable water soluble salts include potassium hydroxide (KOH), sodium hydroxide (NaOH), substituted ammonium hydroxides, such as tetramethylammonium hydroxide and ammonium hydroxide. Bases with low water solubility such as lithium hydroxide, aluminum hydroxide, and calcium hydroxide are not useful in processes of the invention due to solution saturation below useful concentrations. Useful concentrations of the etchant solutions vary depending upon the thickness of the LCP film to be etched, as well as the type and thickness of the photoresist chosen. Typical useful concentrations range from 35wt.% to 55wt.%, preferably from 40wt.% to 50wt.% of a suitable salt and from 10wt.% to 35wt.%, preferably from 15wt.% to 30wt.% of a solubilizer. The use of KOH is preferred for producing a highly alkaline solution since KOH-containing etchants provide

optimally etched features in the shortest amount of time. One highly preferred embodiment, uses potassium hydroxide at a concentration of from 43wt.% to 48wt.%.

Solubilizers for etchant solutions according to the present invention may be selected from the group consisting of amines, including ethylene diamine, propylene diamine and the like, and alkanolamines such as ethanolamine, propanolamine and the like. Under the conditions of etching, unmasked areas of an LCP film substrate become soluble by action of the solubilizer in the presence of a sufficiently concentrated aqueous solution of e.g. an alkali metal salt. The time required for etching depends upon the type and thickness of the film to be etched and is typically from 30 seconds to 10 minutes.

10 Using a preferred etchant solution, of concentrated KOH and ethanolamine, the etching time for a 50 μm (2.0 mil) LCP film is from 30 seconds to 240 seconds. The etching solution is generally at a temperature of 50° C (122° F) to 120° C (248° F) preferably from 70° C (160° F) to 95° C (200° F).

In the past, flexible circuits that include a liquid crystal polymer substrate typically required a starting material having a metal surface coating on at least one side of a polymer film. Circuit patterns were then developed using a subtractive process to remove metal from those areas not requiring conductive circuit traces. The subtractive method was necessary to overcome previous difficulties with the use of vacuum sputtering or vapor evaporation processes for applying metal to liquid crystal polymers without the use of a bonding agent.

The use of etching solutions according to the present invention facilitates surface preparation of liquid crystal polymers for deposition and adhesion of metal, either as a continuous metal coat or preferably in the form of a metal pattern. Surface preparation for improved metal adhesion promotes the use of additive methods that produce metal patterns on liquid crystal polymer substrates. Suitable means for metal application may include vacuum sputtering, or vapor evaporation, or electroless plating or the like after suitable surface treatment of the liquid crystal polymer. A primary objective of surface treatment is to promote compatibility between a metal deposit and the liquid crystal polymer. With suitable compatibility, a metal deposit adheres to the polymer surface producing a bond that resists separation.

Suitable surface treatment of liquid crystal polymers includes a process according to the present invention. This process allows selective plating of metal trace patterns on

LCP film. Using an additive technique, the process requires initial film surface modification before the application of material that provides catalytic sites for metal deposition. Formation of catalytic sites may also be referred to as metal seeding. Further processing of a catalyzed liquid crystal polymer surface produces a pattern of circuit traces. Required steps include lamination of a resist over a catalyzed surface and development of a pattern in the resist. The development process exposes catalyzed sites on the liquid crystal polymer. A number of metal deposition treatments may then be needed to add metal according to the pattern formed in the resist. Metal deposition may be accomplished using a combination of techniques including electroless plating and electrolytic plating to produce metal traces corresponding to the pattern of the catalyzed sites. Copper or nickel or gold or combinations thereof may be deposited as described above. Following the additive process for conductive circuit formation, optional etching of vias and removal of residual resist material provides a finished circuit structure. In this process the bond strength of metal to liquid crystal polymer is sufficient without the use of a tie layer. As an additional benefit, the process limits exposure of the liquid crystal polymer substrate to elevated temperature.

A circuit augmentation process according to the present invention applies preferably to the manufacture of two-layer flexible circuits formed on surfaces of liquid crystal polymer films without using bonding adhesive layers. The additive metal process achieves conductive trace formation using electroless plating of fine pitch structures excluding bussline features.

The present invention allows change in the contour of through holes, vias and blind vias depending upon the concentration of solubilizer in the etchant and the temperature of etching. A solution of etchant containing 10wt.% to 15wt.% ethanolamine provides a through hole angle of 25° to 35° while ethanolamine concentration of 15wt.% to 30wt.% in the etchant solution provides a through hole side-wall angle of 35° to 45°. The side-wall angle also changes with alkali metal hydroxide concentration in the etchant solution, such that over the concentration range of from 35wt.% KOH to 55wt.% KOH the angle of the side-wall changes from 25° to 55°. Modification of the angle of the side-wall is not possible using drilling, punching or laser ablation. In these latter cases, the walls of through holes are substantially parallel.

The manufacture of flexible circuits according to the present invention comprises the step of etching which may be used in conjunction with various known pre-etching and post-etching procedures. The sequence of such procedures may be varied as desired for the particular application. A typical sequence of steps may be described as follows:

5 Aqueous processible photoresists are laminated over both sides of a substrate having a polymeric film side and a copper side (available from W.L. Gore and Assoc. of Japan and Kuraray Corp. of Japan), using standard laminating techniques. Typically, the substrate has a polymeric film layer of from 25 μm to 125 μm , with the copper layer being from 1 μm to 5 μm thick.

10 The thickness of the photoresist is from 25 μm to 50 μm . Upon imagewise exposure of both sides of the photoresist to ultraviolet light or the like, through a mask, the exposed portions of the photoresist become insoluble by crosslinking. The resist is then developed, by removal of unexposed polymer with a dilute aqueous solution, e.g., a 0.5-1.5% sodium carbonate solution, until desired patterns are obtained on both sides of the
15 laminate. The copper side of the laminate is then further plated to desired thickness. Chemical etching of the LCP film then proceeds by placing the laminate in a bath of etchant solution, as previously described, at a temperature of 50° C to 120° C to etch away portions of the LCP polymer not covered by the crosslinked resist. This exposes certain areas of the original thin copper layer. The resist is then stripped from both sides of the
20 laminate in a 2-5% solution of an alkali metal hydroxide at 25° C to 80° C, preferably from 25° C to 60° C. Subsequently, exposed portions of the original thin copper layer are etched using an etchant that does not harm the LCP film, e.g., PERMA-ETCH, available from Electrochemicals, Inc.

 In an alternate process, the aqueous processible photoresists are laminated onto
25 both sides of a substrate having a LCP film side and a copper side, using standard laminating techniques. The substrate consists of a polymeric film layer 25 μm to 125 μm thick with the copper layer being from 9 μm to 40 μm thick. The photoresist is then exposed on both sides to ultraviolet light or the like, through a suitable mask, crosslinking the exposed portions of the resist. The image is then developed with a dilute aqueous
30 solution until desired patterns are obtained on both sides of the laminate. The copper layer is then etched to obtain circuitry, and portions of the polymeric layer thus become exposed. An additional layer of aqueous photoresist is then laminated over the first resist

on the copper side and crosslinked by flood exposure to a radiation source in order to protect exposed polymeric film surface (on the copper side) from further etching. Areas of the polymeric film (on the film side) not covered by the crosslinked resist are then etched with the etchant solution containing an alkali metal salt and LCP solubilizer at a
 5 temperature of 70° C to 120° C, and the photoresists are then stripped from both sides with a dilute basic solution, as previously described.

To create finished products such as flexible circuits, interconnect bonding tape for "TAB" (tape automated bonding) processes, microflex circuits, and the like, conventional processing may be used to add multiple layers and plate areas of copper with gold, tin, or
 10 nickel for subsequent soldering procedures and the like as required for reliable device interconnection.

The following examples are meant to be illustrative and are not intended to limit the scope of the invention which is expressed solely by the claims.

15 Experimental

Experiments were conducted with LCP materials described as follows:

Film A - a LCP/copper laminate (W.L. Gore and Associates of Japan).

Film B - a LCP/copper laminate K-CT (Kuraray Corporation of Japan).

Film C - a LCP/copper laminate R-OC (Kuraray Corporation of Japan).

20 Film D - a LCP film 50µm thick (W.L. Gore and Associates of Japan).

Film E - a LCP film 50µm thick (Kuraray Corporation of Japan).

The etching rate of liquid crystal polymers was estimated by determining the time required to dissolve a film of a selected polymer in an etchant solution. Film A was further
 25 tested for etching performance of circuit features using resist coated film. Etchant solution performance was visually assessed using a ranking scheme wherein 1 = Satisfactory etching and appearance.

3 = Marginal performance or attack of the resist.

5 = Unsatisfactory performance

30 Etchant Solutions

Table 1 shows the compositions of etchant solutions 1-8 suitable, according to the present invention, for effectively etching liquid crystal polymer films as well as

compositions C1-C6 that generally do not satisfy requirements for liquid crystal film etching.

Table 1 - Etchant Solution Compositions 1-8 and C1-C6

Etchant Solution	Composition - wt.% %EA*/%KOH/%Water
1	20/40/40
2	33/40/27
3	10/45/45
4	20/45/35
5	19.3/48.2/32.5
6	10/50/50
7	20/38/42
8	15/44.7/40.3
C1	21.9/31.2/46.9
C2	33/33/34
C3	15.7/33.7/50.6
C4	17.6/35.6/45.8
C5	0/40/60
C6	0/50/50

5

*EA = Ethanolamine KOH = Potassium Hydroxide

Testing Conditions for Liquid Crystal Polymer Film Solubility in Etchant Solutions

10 Samples of 50 μ m (2.0 mil) thick liquid crystal polymer film, 1cm x 1cm square, were submerged in etchant solutions contained in an etchant bath. The temperature of the etchant was maintained at 85°C and the time was recorded for dissolution of film samples in the etchant solutions shown in Table 1. Times exceeding 10 minutes indicate poor etchant performance. Although some etchant mixtures rapidly dissolved the liquid crystal polymer samples, they did not perform well when the liquid crystal polymer was coated
15 with an aqueous developable film resist material (see Table 2 solutions C1-C4).

Testing Conditions for Resist Coated Liquid Crystal Polymer Film

Two layers of 50 μm thick aqueous resists, available from DuPont under the tradename RISTON™ 4720, were laminated with heated rubber rolls to a flexible substrate consisting of 50 μm (2.0 mil) of LCP film on one side and copper on the other.

- 5 The laminate was then exposed with ultraviolet (UV) light through a phototool or mask on each side and developed with 0.75% aqueous solution of sodium carbonate on both sides to obtain desired image of circuitry. Copper was then plated on the copper side of the laminate to 35 μm in thickness. The LCP side was then etched by dipping into an etchant bath containing one of the compositions listed in Table 1. The temperature of the etchant bath was controlled at 85°C (185°F). Each resist was then washed with water, and the resist was stripped with 2.5% KOH at 25°C to 85°C. The condition of etched films was evaluated to determine etchant performance with Film A as recorded in Table 2.

Table 2 - Solution and Etching Times for Film A

Etchant Solution	LCP Film	Time (min) Film Only	Time (min) +Resist	Etchant Performance
1	A	6.3	8.5	1
2	A	1.6	5.0	1
3	A	4.5	11.0	3
4	A	2.4	5.5	1
5	A	2.4	-	1
6	A	3.0	6.5	1
7	A	-	6.5	1
8	A	-	6.0	1
C1	A	4.0	10	5
C2	A	2.7	6.5	3
C3	A	5.2	10.0	5
C4	A	2.7	9.5	5
C5	A	26.4	-	5
C6	A	24.6	-	5

Table 3 - Solution and Etching Times for Film B

Etchant Solution	LCP Film	Time (min) Film Only	Etchant Performance
2	B	3.2	1
3	B	5.5	1
4	B	5.0	1
6	B	2.2	1
C1	B	>35.0	5
C2	B	14.2	5
C3	B	>35.0	5
C4	B	>30.0	5
C5	B	>72.0	5

5

Table 4 - Solution and Etching Times for Film C

Etchant Solution	LCP Film	Time (min) Film Only	Etchant Performance
2	C	3.5	1
3	C	5.7	1
4	C	5.2	1
6	C	2.3	1
C1	C	>35.0	5
C2	C	>10.0	5
C3	C	>60.0	5
C4	C	>30.0	5
C5	C	>72.0	5

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Test Methods

Qualitative Adhesion Test (ASTM D3359-93)

The test method (ASTM D3359-93) requires the formation of an X-cut in the film of conductive metal applied to a liquid crystal polymer substrate. Pressure sensitive tape, applied over the X-cut, provides a qualitative measure of metal-to-substrate adhesion when removed from the test material. After removal of the test tape, the metal-to-substrate adhesion may be assessed using a suitable scale to indicate release or retention of metal.

Adhesion of Plated Metal to Liquid Crystal Polymer Film

The adhesion or bonding quality of conductors to the surface of liquid crystal polymer film was measured using the procedure outlined in standard test method IPC-TM 650. An Instron peel tester, operating at a rate of 1.2cm/minute, was used as the test machine required by this test method.

Surface Preparation and Additive Metal Plating

Example 1

Liquid crystal polymer film (Film D) obtained from W.L. Gore and Associates was chemically etched using a mixture of 45% KOH and 20% ethanolamine at 85°C (185°F) for 5-10 seconds. The modified film was immersed in a tin(II) solution comprising 10g stannous chloride and 40ml 35% hydrochloric acid per liter of solution. After an immersion time of approximately 15 seconds at room temperature the treated film was washed with deionized water. Immersion of the treated film in a palladium(II) solution, containing 0.25g palladium(II) chloride and 2.5ml 35% hydrochloric acid per liter of solution, for approximately 15 seconds provided a catalyzed film also referred to herein as a metal seeded film. Deionized water was used to rinse the film after immersion in the palladium(II) solution. The metal seeded film was plated in electroless nickel solution (UIC Nimuden SX available from Uyemura International Corporation, Ontario, CA) at 85°C. Plating times were 2 to 3 minutes to obtain several different thickness of samples. The plated thickness depends upon the plating time. There was no delamination with the Qualitative Adhesion tape peel test. In contrast, samples plated without chemical etching, as described above, showed evidence of metal delamination from the liquid crystal polymer surface under the conditions of qualitative adhesion testing.

Example 2

The process of Example 1 was repeated using a liquid crystal polymer film designated as CT grade film available from Kuraray Corporation of Japan. After metal seeding film surfaces, previously etched for times between 20 seconds and 60 seconds, a metal deposit from a nickel electroless plating bath exhibited metal to film adhesion without delamination under the conditions of the tape peel test. In contrast, samples plated without chemical etching, as described above, showed evidence of metal delamination from the liquid crystal polymer surface under the conditions of qualitative adhesion testing.

Example 3

A sample of nickel-plated film from Example 1 was immersed at 45°C for 60 seconds in an electroless copper plating bath available as ENTHONE OMI Cu-872 from Enthone-OMI Incorporated. Copper metal, added by this process, adhered well to nickel traces produced by Example 1

Example 4

This example shows improved bonding of sputtered metal coatings to liquid crystal polymers previously treated using etchant solutions according to the present invention. In this case, a liquid crystal polymer film, etched as described in Example 1, was inserted into a bench top sputter coater to coat the film with Pd/Au at a current of 10 mA for 25 seconds. Prior art information suggests that the resulting metal deposit has a thickness in the range of 0.04 μ m to 0.5 μ m. Following sputter coating, the film was immersed at 45°C for 60 seconds in an electroless copper plating bath available as ENTHONE OMI Cu-872 from Enthone-OMI Incorporated. The plated copper had a resistivity of less than 1.0 ohm-cm and was not removed during testing for delamination using the Qualitative Adhesion adhesive tape peel test.

Example C1

Example C1 involved the application of a protective resist to a liquid crystal polymer film available from W.L. Gore and Associates. Removal of portions of the resist

revealed a pattern of the exposed surface of the liquid crystal polymer film. The exposed polymer was corona treated using a hand torch device applied for 30 seconds. After corona treatment, the modified film was immersed in tin(II) solution for approximately 15 seconds and rinsed as described in Example 1. Immersion of the treated film in a

5 palladium(II) solution, containing 0.25g palladium(II) chloride and 2.5ml 35% hydrochloric acid per liter of solution, for approximately 15 seconds provided a metal seeded film. Deionized water was used to rinse the film after immersion in the palladium(II) solution.. The metal seeded film was plated in electroless copper solution at

10 50°C. Plating times of 1 to 2 minutes produced samples of differing metal thickness depending on the development time. The plated copper showed good conductivity but poor adhesion to the liquid crystal polymer. This observation is significant considering that the process of corona treatment and metal seeding is used as a conventional method for seeding polyimide substrates.

15 Table 5 – Qualitative Metal Adhesion to Liquid Crystal Polymer Film

Example	Qualitative Adhesion Test
1	No metal delamination
2	No metal delamination
3	No metal delamination
4	No metal delamination
C1	Metal delamination observed

Example 5

20 Etchant solutions, according to the present invention, facilitate the use of vacuum sputtering as a process for depositing an adherent metal layer on a liquid crystal polymer film. Samples of a suitable 50 μ m (2 mil) LCP film, available from W.L. Gore & Associates, were processed without treatment or treated with etchant solution as indicated in Table 6. After treatment, each film was placed in a vacuum chamber and an adherent

25 metal deposit was applied using conventional sputtering techniques to apply chromium to a thickness from 3nm to 20nm. A layer of copper approximately 100nm was sputtered

over the chromium of the metal-seeded liquid crystal polymer films. The resulting sputtered films were electroplated to increase the copper thickness to approximately 10 μ m.

Metal test patterns required by the IPC-TM 650 test method were generated using a conventional subtractive process for printed circuit preparation. Thereafter, Instron peel test results, listed in Table 6, revealed significant improvement of metal to liquid crystal polymer adhesion after polymer surface treatment using chemical etching compositions according to the present invention.

Table 6 - Effect of Surface Treatment on Metal Adhesion

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Sample Condition	Peel strength N/mm (lb/in)
No treatment	0.14 (0.79)
Etchant at 75°C for 5.0 seconds	0.41 (2.32)
Etchant at 80°C for 10.0 seconds	0.41 (2.36)
Etchant at 85°C for 10.0 seconds	0.42 (2.42)

Example 6

Example 6 is similar to example 5 except for the use of conventional sputtering techniques to deposit metal on a moving film, suspended between a pair of rolls. The film provided in roll-to-roll form was, as before, 50 μ m (2.0mil) thick liquid crystal polymer film. Before loading into the sputtering apparatus, each roll of film was either left untreated or chemically etched at 50°C (120°F) at 72 inches/minute line speed. Table 7 records the results for untreated film and for two different rolls of liquid crystal polymer film chemically etched under the same conditions. In a sequence of treatments, sputtered chromium was first applied to each film to deposit a layer of metal from 3nm to 20nm thick. Each liquid crystal polymer film then received a coating of copper having a thickness from 100nm to 200nm copper. The resulting sputtered films were then treated to augment the sputtered copper with from 10 μ m to 35 μ m of electroplated copper.

Metal test patterns required by the IPC-TM 650 test method were generated using a conventional subtractive process for printed circuit preparation. Once again, Instron peel test results, listed in Table 7, revealed significant improvement of metal to liquid crystal polymer adhesion after polymer surface treatment using chemical etching compositions.

Table 7 - Effect of Surface Treatment on Metal Adhesion

Sample Condition	Copper thickness (μm)	Peel strength N/mm (lb/in)
No treatment	10	0.16 (0.9)
Etchant at 50°C at 72ipm	10	0.54 (3.1)
Etchant at 50°C at 72ipm	35	1.0 (5.7)

5 Preliminary treatment by etchants, according to the present invention, provides improvement of metal to polymer adhesion using metallization processes involving either electroless plating or vacuum deposition, e.g. sputtering. As described above, an etched liquid crystal polymer may be produced using either a batch process or a continuous roll-to-roll process.

10 Flexible circuits comprising a liquid crystal polymer film, and methods for processing such a film, have been described herein. Film processing according to the present invention improves the bond between film substrate and metal and facilitates the preparation of additive conductive circuit patterns having through-holes and related shaped voids formed therein at elevated temperature using an aqueous etchant solution has been described herein. Those of skill in the art will appreciate that, in light of the present
15 disclosure, changes may be made to the embodiments described herein without departing from the spirit and scope of the present invention.

Claims

What is claimed is:

- 5 1. A process for producing a metal-seeded liquid crystal polymer comprising the steps of:
- providing a liquid crystal polymer substrate;
 - applying an aqueous solution comprising an alkali metal hydroxide and a
 - 10 polymer substrate;
 - depositing an adherent metal layer on said etched liquid crystal polymer substrate.
2. The process of claim 1, wherein said alkali metal hydroxide is selected from the group consisting of sodium hydroxide and potassium hydroxide.
- 15 3. The process of claim 1, wherein said solubilizer is selected from the group consisting of ethylene diamine, propylene diamine, ethanolamine and propanolamine.
4. The process of claim 1, wherein said aqueous solution comprises from 35wt% to
- 20 55wt% of said alkali metal salt preferably from 40wt% to 50wt% of said alkali metal salt.
5. The process of claim 1, wherein said aqueous solution comprises from 10wt% to 35wt% of said solubilizer preferably from 15wt% to 30wt% of said solubilizer.
- 25 6. The process of claim 1, wherein said applying said aqueous solution requires a time from 10 seconds to 10 minutes at a temperature from 50°C to 120°C, preferably 70° to 95°C.

INTERNATIONAL SEARCH REPORT

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According to International Patent Classification (IPC) or to both national classification and IPC		
B. FIELDS SEARCHED		
Minimum documentation searched (classification system followed by classification symbols) IPC 7 H05K		
Documentation searched other than minimum documentation to the extent that such documents are included in the fields searched		
Electronic data base consulted during the international search (name of data base and, where practical, search terms used) EPO-Internal, PAJ		
C. DOCUMENTS CONSIDERED TO BE RELEVANT		
Category °	Citation of document, with indication, where appropriate, of the relevant passages	Relevant to claim No.
A	EP 0 697 278 A (KURARAY CO ;HOECHST CELANESE CORP (US)) 21 February 1996 (1996-02-21) the whole document -----	1
<input type="checkbox"/> Further documents are listed in the continuation of box C. <input checked="" type="checkbox"/> Patent family members are listed in annex.		
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Information on patent family members

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Patent document cited in search report		Publication date		Patent family member(s)	Publication date
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